

CLAIMS:

1. A photomask blank comprising a transparent substrate by which exposure light is transmitted, at least one layer  
5 of light-shielding film and at least one layer of antireflective film both on the substrate, and a seed layer disposed between the transparent substrate and the light-shielding film or the antireflective film, said seed layer being formed of a chromium material containing at least one  
10 of oxygen, nitrogen and carbon.
2. The photomask blank of claim 1 wherein said light-shielding film or said antireflective film is formed of a chromium material containing at least one of oxygen,  
15 nitrogen and carbon.
3. The photomask blank of claim 1 wherein said seed layer has a thickness of 0.5 to 10 nm.
- 20 4. The photomask blank of claim 1 having a surface roughness (RMS) of up to 0.9 nm.
5. A photomask fabricated by lithographically patterning the photomask blank of claim 1.